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AMENDMENT TRANSMITTAL LETTER				Docket No. 3273-0196PUS1
Application No. 10/519,998-Conf. #5132	Filing Date January 5, 2005	Examiner J. S. Y. Chu	Art Unit 1752	
Applicant(s): Shigeki KAMBARA et al.				
Invention: PHOTORESIST RESIN AND PHOTORESIST RESIN COMPOSITION				
MS Amendment Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450				
Transmitted herewith is an amendment in the above-identified application.				
The fee has been calculated and is transmitted as shown below.				
CLAIMS AS AMENDED				
	Claims Remaining After Amendment	Highest Number Previously Paid	Number Extra Claims Present	Rate
Total Claims	8	- 20 =		x
Independent Claims	2	- 3 =		x
Multiple Dependent Claims (check if applicable) <input type="checkbox"/>				
Other fee (please specify):				
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT:				0.00
<input checked="" type="checkbox"/> Large Entity <input type="checkbox"/> Small Entity <input checked="" type="checkbox"/> No additional fee is required for this amendment. <input type="checkbox"/> Please charge Deposit Account No. _____ in the amount of \$ _____. A duplicate copy of this sheet is enclosed. <input type="checkbox"/> A check in the amount of \$ _____ is enclosed. <input type="checkbox"/> Payment by credit card. Form PTO-2038 is attached. <input checked="" type="checkbox"/> The Director is hereby authorized to charge and credit Deposit Account No. <u>02-2448</u> as described below. A duplicate copy of this sheet is enclosed. <input checked="" type="checkbox"/> Credit any overpayment. <input checked="" type="checkbox"/> Charge any additional filing or application processing fees required under 37 CFR 1.16 and 1.17.				
<u>ny/n-ee # 36,623</u> <u>R</u> Marc S. Weiner Attorney Reg. No.: 32,181				
Dated: May 17, 2006				
BIRCH, STEWART, KOLASCH & BIRCH, LLP 8110 Gatehouse Road Suite 100 East P.O. Box 747 Falls Church, Virginia 22040-0747 (703) 205-8000				



Docket No.: 3273-0196PUS1
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Shigeki KAMBARA, *et al.*

Conf.: 5132

Application No.: January 5, 2005

Art Unit: 1752

Filed: January 5, 2005

Examiner: John CHU

For: PHOTORESIST RESIN AND PHOTORESIST
RESIN COMPOSITION

AMENDMENT UNDER 37 CFR 1.111

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INTRODUCTORY COMMENTS

Responsive to the Office Action of February 17, 2006, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

This response includes:

Amended Claim Set;

Remarks; and

Joel R. Fried, "Polymer Science & Technology, Second Edition", Prentice Hall,
pages 15-17, 128, 129, and 142-145.